

CHE323/CHE384
 Chemical Processes for Micro- and Nanofabrication
www.lithoguru.com/scientist/CHE323

Lecture 38
Lithography:
Introduction

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Reading:
 Chapter 7, *Fabrication Engineering at the Micro- and Nanoscale*, 4th edition, Campbell

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What is Lithography?

- In the art world, lithography is a two-century-old printing technology used to make prints and posters

- In the semiconductor world, lithography is the printing technology used to mass-produce chips like microprocessors, memory and flash that are at the heart of electronic devices

Flash chip circa 2009

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Defining Lithography

li · thog · ra · phy, n. [*<Gr. lithos, stone + graphia, to write*]

- a printing technique based on the production of a three-dimensional relief image on a substrate (writing on stones).

Lithography for chip making is so impressive because it mass-produces things that are incredibly small.

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Motivation (Why care about lithography?)

- Why is lithography so important?
 - 50% of the cost of making a modern chip (integrated circuit) is litho cost
 - Improvements in chip cost and performance (Moore's Law) have historically been gated by lithography capability
- Chip companies, governments, and universities continue to invest large sums in lithography R&D
 - The hope is to keep Moore's Law going

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Why Size Matters

1961

Feature size = 25 microns
(one thousandth of an inch)

→

2011

Feature size = 25 nanometers
(one millionth of an inch)

- We cram more transistors onto a chip by making each transistor smaller
 - Lithography improvements must enable the printing of smaller features *without* significantly increasing the cost of making the chip

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A Note on "Small"

Human Hair
~70 micron

(www.uaberta.ca/~mingchen)

Red Blood Cell
~7 micron

Red Light Wavelength
~700 nanometer

Retrovirus
~70 nanometer

Flash Memory (20 nm)

Patterns printed with lithography to make transistors are as small as 20 nm today, and still getting smaller!

Intel FinFET (40 nm)

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Subtractive Patterning

- Patterning Sequence (example)
 - Deposit polysilicon (for example) on wafer
 - Deposit photoresist layer on top of polysilicon
 - Expose and develop photoresist to create pattern
 - Etch pattern into polysilicon using resist as mask
 - Strip away the resist
 - Repeat 20 – 60 times to make a chip

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Lithography – The Basics

- Ingredients of a Lithography System
 - A master pattern to be reproduced called a photomask
 - A photosensitive film called a photoresist
 - A special camera (called a stepper or a scanner) that projects an image of the photomask into the photoresist
 - A tool for processing the photoresist (coating, baking, developing) called a track

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Lithography Sequence

Track and Stepper/Scanner combined into a "photocell"

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Example Lithography Tools

From Nikon Corp. From ASML

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Example Tracks

TEL Lithius Plus (from Tokyo Electron) SVG 88 (Silicon Valley Group)

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Lecture 38: What have we Learned?

- Give two important reasons why lithography is one of the most critical technologies in semiconductor manufacturing?
- What are the basic steps in a lithography sequence?
- What are the ingredients (tools and materials) of a lithography process?

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